REMARKS

Entry and consideration of this Amendment is respectfully requested.

Additionally, filed concurrently herewith is a sworn translation of the foreign priority document.

Respectfully submitted,

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APPENDIX

VERSION WITH MARKINGS TO SHOW CHANGES MADE

IN THE SPECIFICATION:

The specification is changed as follows:

Amend the specification by inserting before the first line the sentence:

This is a divisional of Application No. 09/322,978 filed June 1, 1999, allowed; the disclosure of which is incorporated herein by reference.

Page 1, 2nd paragraph, is changed as follows:

Positive photoresist compositions comprising an alkali-soluble resin and a quinonediazide ester have been satisfactorily applied in [practical to] <u>practice for</u> the production of semiconductor devices and liquid-crystal display devices, since they have excellent definition, sensitivity and etching resistance.

The paragraph bridging pages 8-9 is changed as follows:

FIG. 1 illustrates a developing process and locations for the evaluation of sensitivity on resist [patterns] patterns in the examples of the invention;

IN THE CLAIMS:

Claim 5 is canceled.

The claims are amended as follows:

1 (Amended). A positive photoresist composition comprising

- (A) an alkali soluble resin,
- (B) a photosensitizer containing a quinonediazide ester of a compound of the following formula (I):

wherein each of R1 and R2 is independently a methyl group or an ethyl group, and

(C) at least one compound of phenol group-containing compounds having structural formula (C1) and having an elution time in the range from 6 to 30 minutes in high performance liquid chromatography, said high performance liquid chromatography being conducted under the following conditions: eluent: a mixed solvent of water:tetrahydrofuran:methanol = 40:24:36 (by weight); column: 4.6 mm (diameter) x 150 mm (length) containing 5 μm silica gel as a filler (carbon content being about 15%); column temperature: 45.0°C; and supply rate of eluent: 0.700 ml/min

Claims 7-21 are added as new claims.